

CMOS structure

Figure 1

PRIOR ART

Poly-Si

Spacer (SiO_2 or SiN_x)

SiO_2

n^+ or p^+

n^+ or p^+

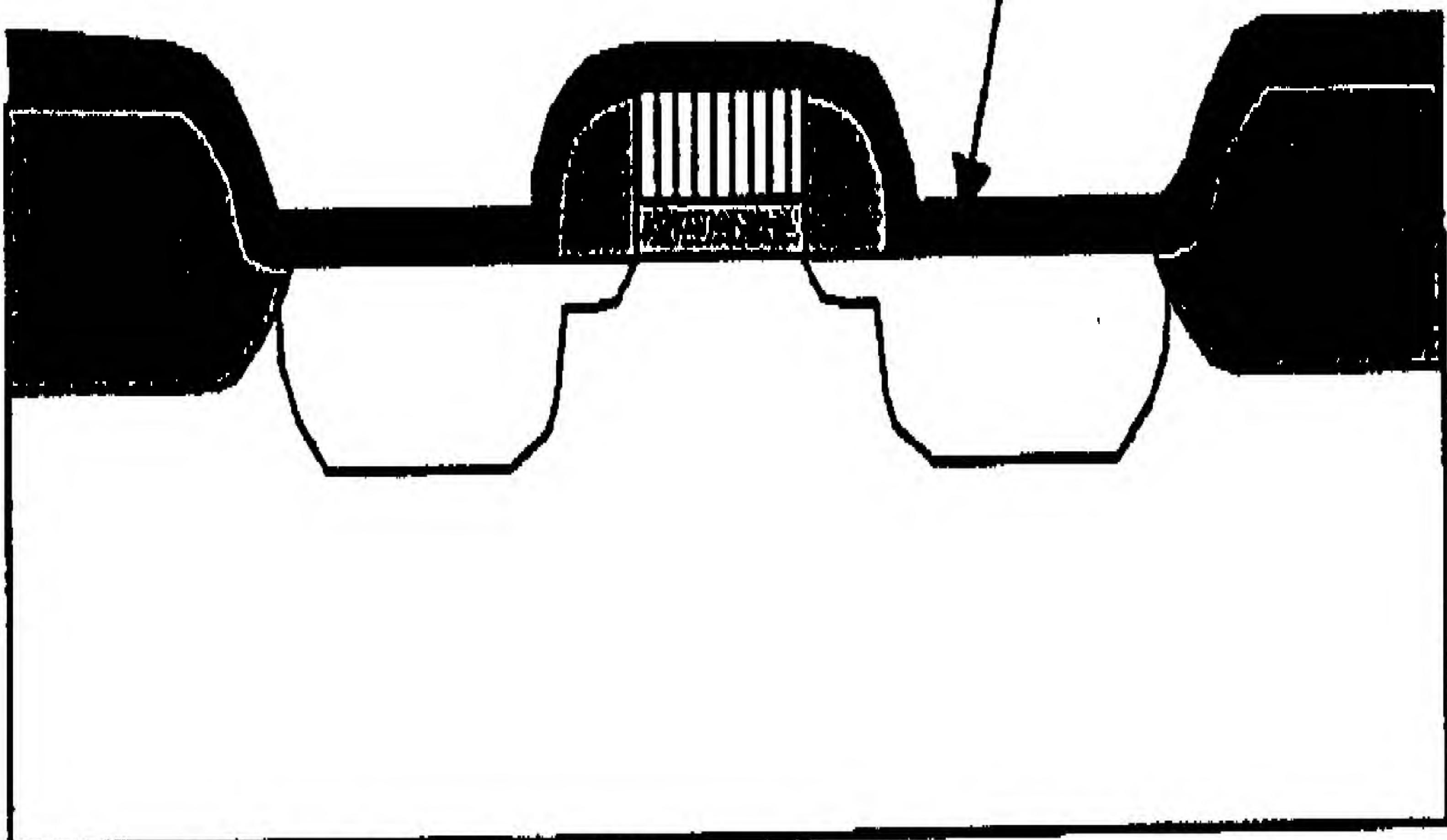
SiO_2

Silicon substrate

(1) Before metal deposition

Figure 2 (1)

Metal film



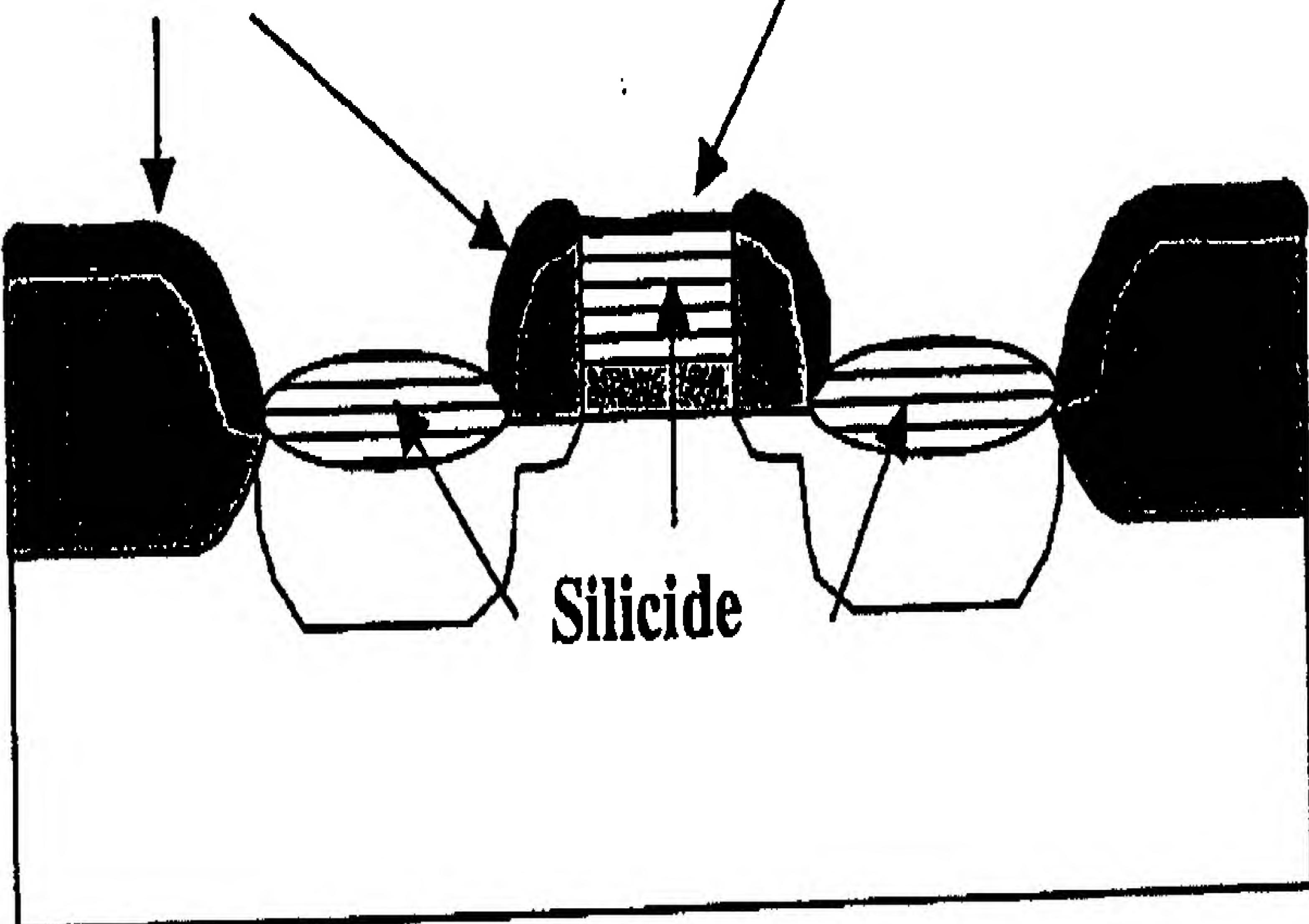
(2) After metal deposition

Figure 2(2)

Residual metal
layer (thin)

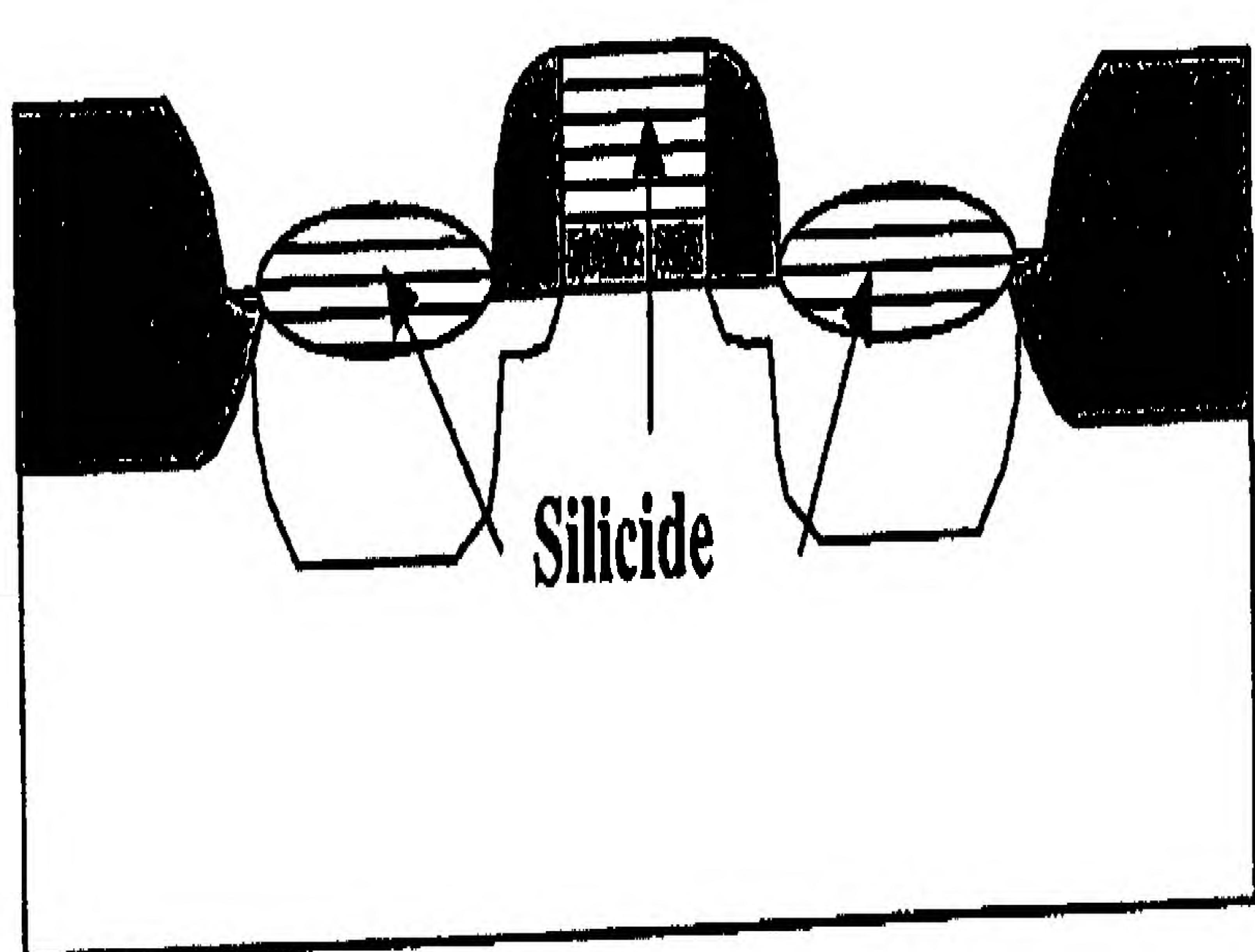
Unreacted metal layer

Silicide



(3) After silicide formation

Figure 2 (3)



(4) After metal etch-off

Figure 2 (4)

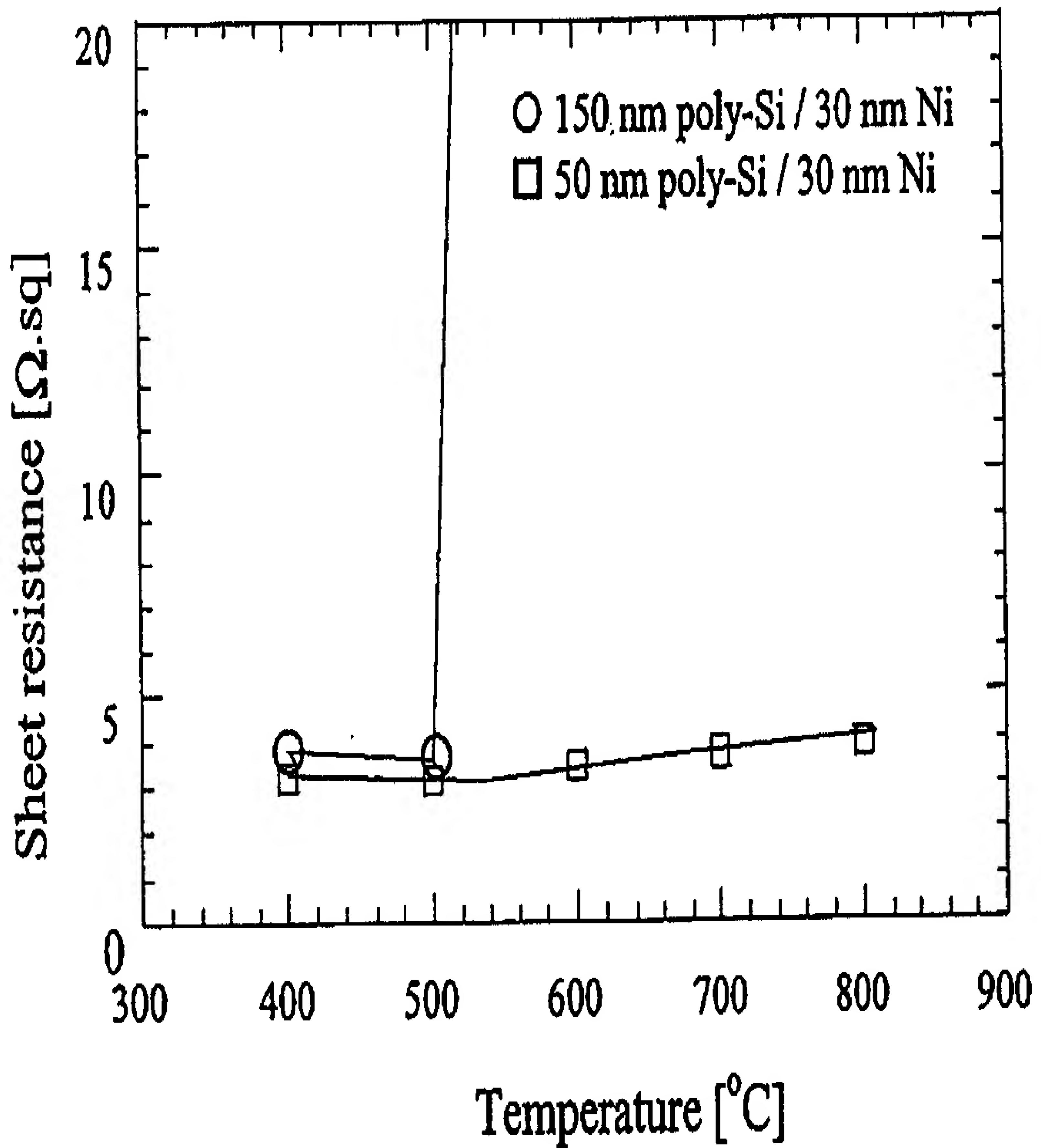


Figure 3

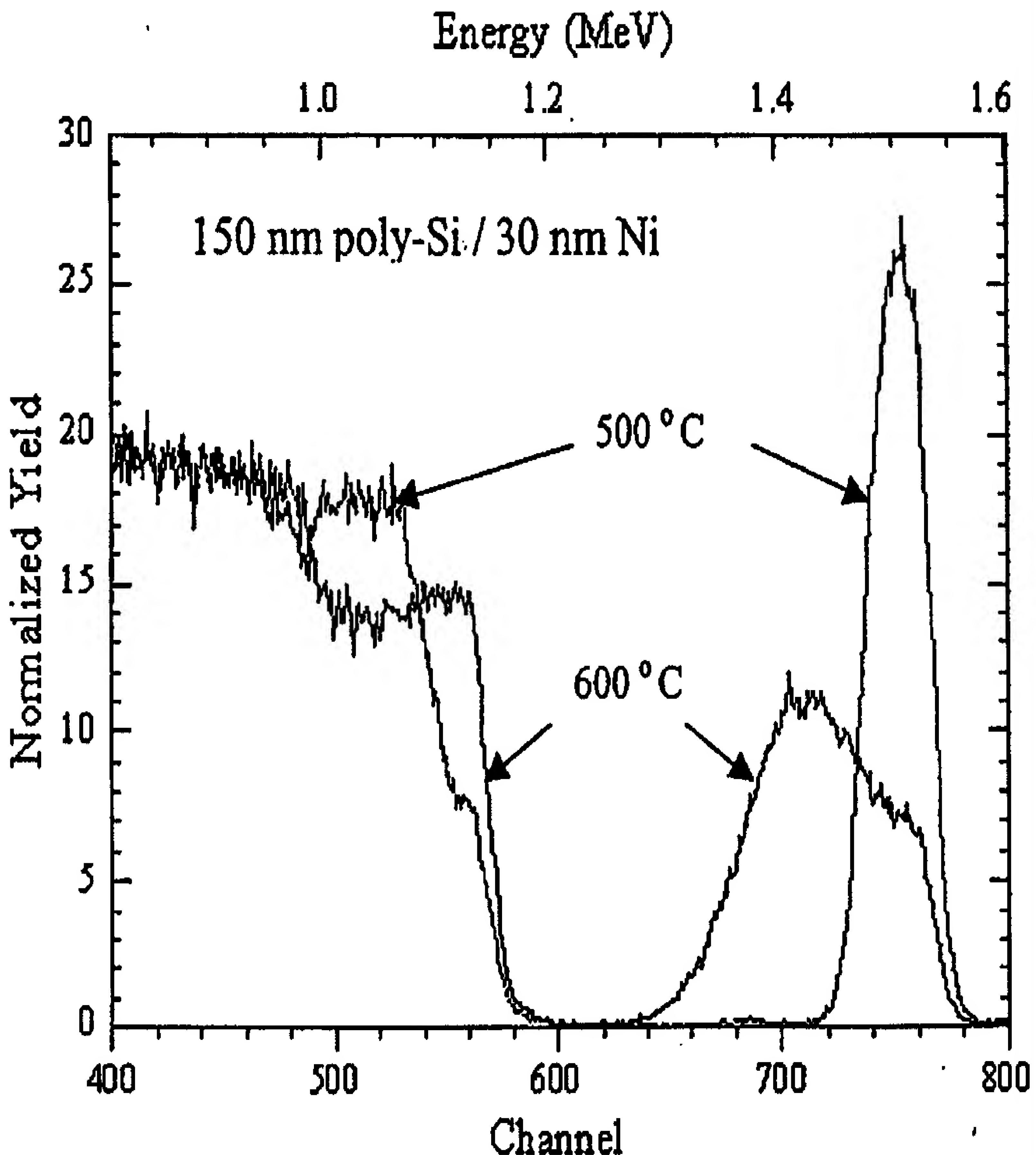


Figure 4